



## **Dr. Ryoung-han Kim**

(Imec, Belgium)



Dr. Ryoung-han Kim serves as the director responsible for design, OPC, and mask tapeout at IMEC, overseeing various R&D initiatives across semiconductor logic, memory, and patterning programs. His expertise lies in technology strategy, patterning, OPC, mask, design and design-technology co-optimization (DTCO).

Currently, Dr. Kim holds the position of associate editor at the JM3 journal and actively contributes to the SPIE advanced lithography and patterning program as the committee member, and served as the program chair from 2021 to 2023. Additionally, he is actively involved in the committee of the IEEE Design Automation Conference (DAC).

Before joining IMEC, Dr. Kim held the role of Sr. Manager of patterning R&D at GLOBALFOUNDRIES, which was spun-off from Advanced Micro Devices, where he initiated his industrial career, gaining valuable pioneering experience in patterning R&D activities. He also was a Senior Member of the technical staff in Texas Instrument's fabless division.

Dr. Kim earned his Ph.D. degree in Electrical Engineering from Texas A&M University, College Station, Texas, USA, and holds B.S. and M.S. degrees from Yonsei University, Seoul, Korea.